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U.S. Patent and Trademark Office		Attorney Docket No.: UMC-96-279			Serial No.: Not Assigned 08/958,460		
INFORMATION DISCLOSURE STATEMENT (Use several sheets if necessary)		Applicants: Chih-Chien Liu, et al.					
		Filing Date: <u>Herewith</u> <u>10/28/97</u>			Art Group: Not Assigned 1700		
U.S. PATENT DOCUMENTS							
Examiner Initial		Document Number		Date	Name	Class	Sub-Class
FOREIGN PATENT DOCUMENTS							
		Document Number		Date	Country	Class	Sub-Class
OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, etc.)							
RA				J.T. Pye, et al., "High-Density Plasma CVD and CMP for 0.25- μ m Intermetal Dielectric Processing," Solid State Technology, December 1995, pp.65-69.			
EXAMINER				DATE CONSIDERED			
<i>Reba Bryant</i>				<u>8/1/99</u>			
EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.							